

### REMARKS

Claims 1-8 remain in this application. Claims 1 and 8 have been amended.

The Office Action rejects claims 2-7 under 35 U.S.C. § 102 over Inokuchi (U.S. Patent 6, 259,960) and rejects claims 1 and 8 under 35 U.S.C. § 103 over Inokuchi. These rejections are respectfully traversed.

The claimed invention is an electron microscope for observing faults and/or objects of a surface or inside of a semiconductor wafer or mask for exposing a semiconductor pattern. It includes a function of letting measurement data of coordinates of said faults and or objects which were obtained with another wafer or mask inspecting apparatus, moving a field of view of the electron microscope based on the measurement data, and simultaneously displaying the coordinates of the fault and or objects, the field of view of the electron microscope, and a vicinity thereof on a display. Thus, the coordinates of the faults and/or objects, the field of view of the electron microscope, and a vicinity are simultaneously displayed on a display, and a deviation between the field of view of the electron microscope corresponding to the coordinates obtained with another wafer or mass inspecting apparatus and the field of view of the electron microscope displayed corresponding thereto is easily corrected, by referring to the positional relation of the coordinates, the field of view, and the vicinity, thereby moving the field of view of the electron microscope to the coordinates.

In contrast, in the cited reference Inokuchi, the field of view of the electron microscope is simply displayed corresponding to the coordinates of the fault and/or objects obtained with another wafer or mass expecting apparatus, without displaying any positional relation of the coordinates, the field of view and the vicinity. When the deviation between the field of view of the electron microscope corresponding to the coordinates obtained with another wafer or mass inspecting apparatus and the field of view of the electron microscope actually displayed corresponding thereto is small, the field of view corresponding to the coordinates of the fault and/or object might be displayed in the electron microscope. However, such deviation is usually fairly large, and the field of view corresponding to the coordinates of the fault and/or objects cannot be displayed on the display. In this situation, the present invention is very useful and is not obvious over Inokuchi. Thus, Inokuchi does not disclose or suggest simultaneously displaying the coordinates of the fault and/or object, the field of view of the electron microscope and vicinity thereof on the display, as recited in the claims of the present application. Accordingly, Applicants request withdrawal of the rejection of the claims.

With entry of this amendment it is believed that all claims remaining in this application will be in condition for allowance. Thus, entry of this amendment and prompt notice is respectfully solicited.

The Examiner is invited to contact the undersigned to discuss any matter concerning this application.

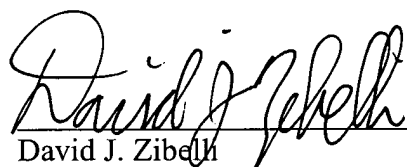
Applicants respectfully request a two month Extension of Time to respond to the Final Rejection of June 4, 2003. The extended period expires November 4, 2003.

The Office is hereby authorized to charge the fee of \$420.00 for a Petition for Extension of Time Under 37 C.F.R. § 1.136(a) and any additional fees under 37 C.F.R. § 1.16 or § 1.17 or credit any overpayment to Deposit Account No. 11-0600.

Respectfully submitted,

KENYON & KENYON

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David J. Zibell  
Registration No. 36,394

KENYON & KENYON  
1500 K Street, N.W., Suite 700  
Washington, D.C. 20005-1257  
Telephone (202) 220-4200  
Facsimile (202) 429-0796  
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